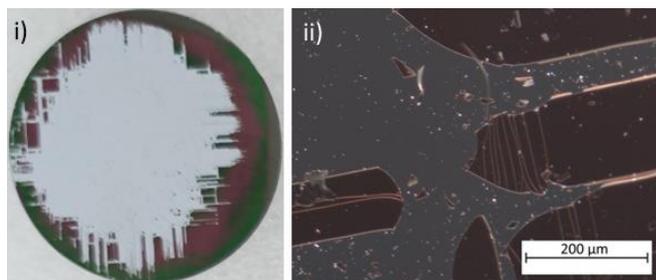
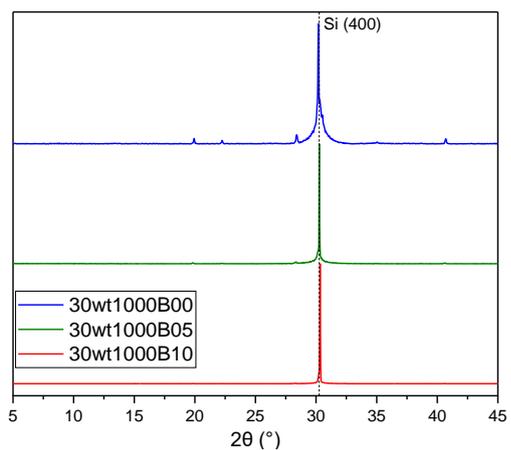


## Supporting Information

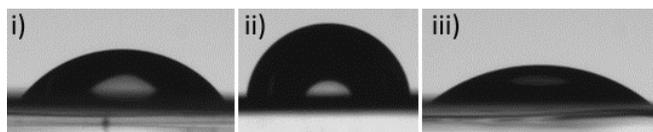


**Figure S1.** i) image and ii) light microscopy image of 35wt1000B05 derived from solution aged for two weeks (6000 rpm) showing strong delamination due to increased coating thickness after aging.

Reflective XRD shows that the coatings prepared from all three precursors remain amorphous after pyrolysis at 1000 °C for two hours. The diffractograms in Figure S2 show a strong Si (400) reflex of the single crystalline wafer, as well as some weak reflexes that are attributed to silicon oxide. Since strong reflexes that would occur for all randomly oriented polycrystalline silicon oxide phases are missing, the peaks are attributed to a thin oxide layer on the monocrystalline substrate.



**Figure S2** XRD spectra of 30wt1000B00, 30wt1000B05 and 30wt1000B10 showing a strong Si (400) reflex of the (100) oriented substrate and minute silicon oxide reflexes.



**Figure S3.** Sessile water droplets on i) Silicon wafer, ii) 30wt250B05, iii) 30wt1000B05.